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March 22, 2001

To: Commissioner of Patents and Trademarks

Washington, D.C. 20231

Fr: George O. Saile, Reg. No. 19,572

20 McIntosh Drive

Poughkeepsie, N.Y. 12603

Subject:

Serial No. 09/764,243 01/19/01

Michael Stephens, Jr.,

Christopher Ematrudo, Jeffrey S. Earl

RETICLE OPTION LAYER DETECTION

METHOD

Grp. Art Unit: 2812

INFORMATION DISCLOSURE STATEMENT

Enclosed is Form PTO-1449, Information Disclosure Citation In An Application.

The following Patents and/or Publications are submitted to comply with the duty of disclosure under CFR 1.97-1.99 and 37 CFR 1.56. Copies of each document is included herewith.

U.S. Patent 5,940,704 to Takeuchi, "Method of Manufacturing a Reference Apparatus", discloses a method of making a reference apparatus for determining current or voltage in nonvolatile memory cells.

VISA-048

- U.S. Patent 5,747,868 to Reddy et al., "Laser Fusible Link Structure for Semiconductor Devices", teaches a method to form polysilicon laser fusible links in an integrated circuit device.
- U.S. Patent 4,758,863 to Nikkel, "Multi-Image Reticle", illustrates a multilevel reticle having multiple masks of integrated circuit patterns.
- U.S. Patent 5,907,492 to Akram et al., "Method for Using Data Regarding Manufacturing Procedures Integrated Circuits (IC's) Have Undergone, Such As Repairs, to Select Procedures the IC's Will Undergo, Such As Additional Repairs", teaches a method for use in an integrated circuit manufacturing process.

Sincerely

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